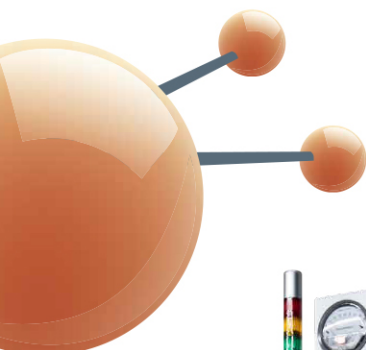


Candi™



The Candi™ system is designed to provide end users with a continuous supply of a low vapor pressure liquid precursor delivered at a steady pressure. It improves safety, reliability and stability of the delivery process.



Applications

Typical applications: liquid precursor supply to Direct Liquid Injection (DLI), on-board bubbler or vaporizer and on-board buffer canister.

Possible precursors:

- BPSG processes: TEOS, TEPO, TEB...
- Low-k dielectrics: 4MS, TMCTS, OMCTS, DMPS, BCHD...
- High-k dielectrics: DMAI, TDMAS, 4DMAS...
- Low-T SiN/SiO: HCDS, SAM.24TM, BTBAS...

Operation

Pressurized inert gas is used to transfer from the canister to an internal process tank and from this process tank to the tool. The process tank allows the continuous dispense of the chemical during a canister change-out.

The patented Candi purge, which uses gas compression and expansion cycles, ensures a safe canister change-out and prevents precursor from contamination.



Several patented features such as the back-up distribution mode, process tank level control and empty canister detection for maximum chemical use, ensure a reliable & cost efficient distribution of the precursor to the process.

Qualification

The Candi is qualified by most tool manufacturers for 300-mm processes:

- Referenced on multiple OEMs (Original Equipment Manufacturers) platforms,
- Pre-defined interfacing with multiple OEMs.

Key benefits

- ✓ **Improved footprint to minimize cost of ownership: 525 x 450mm,**
- ✓ **High flow degas unit able to provide a flow rate up to 240sccm,**
- ✓ **New vacuum detection options available for more reliable purge,**
- ✓ **Enhanced safety with integrated liquid trap to protect the vent line from any chemical release,**
- ✓ **User-friendly new controllers,**
- ✓ **Use of N₂ as purge gas to minimize cost of use.**